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Docket No.: M4065.0453/P453-B
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Eugene P. Marsh et al.

Application No.: 10/657,069

Art Unit: 2822

Filed: September 9, 2003

Examiner: M. Lewis

For: PROCESS FOR LOW TEMPERATURE
ATOMIC LAYER DEPOSITION OF RH

REQUEST FOR RECONSIDERATION

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated April 21, 2004 (Paper No. 04082004), please reconsider the above-identified U.S. patent application in view of the following remarks: